

# ISO 17331:2004-05 (E)

Surface chemical analysis - Chemical methods for the collection of elements from the surface of silicon-wafer working reference materials and their determination by total-reflection X-ray fluorescence (TXRF) spectroscopy

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<b>Contents</b>		<b>Page</b>
Foreword .....		iv
Introduction .....		v
<b>1</b>	<b>Scope .....</b>	<b>1</b>
<b>2</b>	<b>Normative references .....</b>	<b>1</b>
<b>3</b>	<b>Terms and definitions .....</b>	<b>1</b>
<b>4</b>	<b>Abbreviations .....</b>	<b>2</b>
<b>5</b>	<b>Reagents .....</b>	<b>2</b>
<b>6</b>	<b>Apparatus .....</b>	<b>6</b>
<b>7</b>	<b>Specimen preparation and measurement environments .....</b>	<b>6</b>
<b>8</b>	<b>Preparation of calibration specimen .....</b>	<b>6</b>
<b>9</b>	<b>Making calibration curve .....</b>	<b>8</b>
<b>10</b>	<b>Collection of iron and/or nickel from working reference material .....</b>	<b>10</b>
<b>11</b>	<b>Determination of iron and/or nickel of working reference material .....</b>	<b>11</b>
<b>12</b>	<b>Precision .....</b>	<b>11</b>
<b>13</b>	<b>Test report .....</b>	<b>12</b>
	<b>Annex A (informative) International inter-laboratory test results .....</b>	<b>13</b>
	<b>Annex B (informative) International inter-laboratory test results of GF-AAS and ICP-MS .....</b>	<b>16</b>